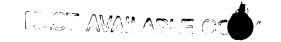


ELOT AVAILABLE W

09/885,319

L Number	Hits	Search Text	DB	09/885, 7 Time stamp
•	11	136/\$.ccls. and (nucleation adj layer)	USPAT;	2002/05/10
		(1200)	US-PGPUB;	12:55
			EPO; JPO;	12.55
			DERWENT	
-	1520	136/249,255,261,262.ccls.	USPAT;	2002/05/10 11:17
	.520	100/247,200,201,202.0013.	US-PGPUB;	2002/03/10 11:17
			EPO; JPO;	
			DERWENT	
-	81	438/74.ccls.	1	2002/05/10 11:17
		430/74.CCIS.	USPAT;	2002/05/10 11:17
			US-PGPUB;	
			EPO; JPO;	
	•	(12/ /240 055 2/4 2/2 420 /74)	DERWENT	
-	16	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
i		(triple adj junction)	US-PGPUB;	11:25
			EPO; JPO;	
			DERWENT	
-	225	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(semiconductor adj substrate)	US-PGPUB;	11:26
			EPO; JPO;	
			DERWENT	
-	30	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(germanium adj substrate)	US-PGPUB;	11:26
			EPO; JPO;	
			DERWENT	
-	11	4835116.URPN.	USPAT	2002/05/10
				12:40
-	23	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(lattice adj parameter)	US-PGPUB;	13:51
			EPO; JPO;	
			DERWENT	
-	61	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(junction near depth)	US-PGPUB;	13:52
			EPO; JPO;	
			DERWENT	
-	1	((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(germanium adj substrate)) and	US-PGPUB;	13:53
		((136/249,255,261,262.ccls. or 438/74.ccls.) and	EPO; JPO;	10.00
		(junction near depth))	DERWENT	
-	1	((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
	-	(junction near depth)) and (germanium near substrate)	US-PGPUB;	13:53
		(ganonominear deprin) and (germaniam near sabstrare)	EPO; JPO;	13.33
•			DERWENT	
_	2	((136/240 255 261 262 colo en 429/74 colo \	i	2002/05/10
-	۷	((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
$\overline{}$		(junction near depth)) and (germanium near2	US-PGPUB;	13:53
		substrate)	EPO; JPO;	
`		//12/ /240 0EE 0/4 0/2 1	DERWENT	
-	2	((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(junction near depth)) and (germanium near3	US-PGPUB;	13:54
		substrate)	EPO; JPO;	
			DERWENT	





	24	((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(junction near depth)) and (semiconductor adj	US-PGPUB;	14:00
		substrate)	EPO; JPO;	
		,	DERWENT	
_	5	(((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(junction near depth)) and (semiconductor adj	US-PGPUB;	14:00
		substrate)) and germanium	EPO; JPO;	
		, <u>, .</u>	DERWENT	
-	12	((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(junction near depth)) and germanium	US-PGPUB;	14:13
			EPO; JPO;	
			DERWENT	
-	7	((136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(junction near depth)) and (two adj step)	US-PGPUB;	14:51
			EPO; JPO;	
			DERWENT	
-	4	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(AMO near2 efficiency)	US-PGPUB;	14:21
		,	EPO; JPO;	
			DERWENT	
-	6	136/\$.ccls. and (AMO near2 efficiency)	USPAT;	2002/05/10
			US-PGPUB;	14:21
			EPO; JPO;	
		·	DERWENT	
-	10	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		((solid adj state) near2 diffusion)	US-PGPUB;	14:53
			EPO; JPO;	
			DERWENT	
-	7	136/\$.ccls. and mocvd and movpe	USPAT;	2002/05/10
			US-PGPUB;	15:17
			EPO; JPO;	
			DERWENT	
-	1547	136/249,255,261,262.ccls. or 438/74.ccls.	USPAT;	2002/05/10
			US-PGPUB;	16:37
			EPO; JPO;	
			DERWENT	
-	1	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(oxide adj desorption)	US-PGPUB;	16:37
			EPO; JPO;	
			DERWENT	
-	0	(136/249,255,261,262.ccls. or 438/74.ccls.) and	USPAT;	2002/05/10
		(oxygen adj desorption)	US-PGPUB;	16:37
			EPO; JPO;	
			DERWENT	